

Device and method for drying waferlike substrates

Abstract

A device for drying waferlike substrates, comprising an element having a horizontal
5 principal extent direction and, transverse to the principal extent direction, a cross-
sectional profile which tapers upward in vertical direction,
wherein the element at its top side has a plurality of support positions which are
suitable for supporting waferlike substrates,
the plurality of support positions are arranged along the principal extent direction,
10 the plurality of support positions are bordered by faces of the element that fall away
starting from the support positions,
at least some of the faces of the element that border the support positions and fall
away have an upper portion and a lower portion, and
the upper portion is more hydrophilic than the lower portion.

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Figure for the Abstract: Fig. 1